

ADVANCED FUNCTIONAL MATERIALS

Supporting Information

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**p-Si/SnO₂/Fe₂O₃ Core/Shell/Shell Nanowire Photocathodes for
Neutral pH Water Splitting**

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Band diagram of p-Si/n-SnO₂/n-Fe₂O₃ css-NW heterojunctions

The band gap of SnO₂ layer sputtered at a RF power of 400 W at room temperature was measured resulting in a band gap of 3.37 eV as shown in Figure S1. The obtained SnO₂ band gap is consistent with that reported elsewhere.^[1] The considered Si and Fe₂O₃ band gaps were 1.11 eV and 2.1 eV, respectively. To draw the band diagram, the Si NW radius, SnO₂ thickness, and Fe₂O₃ NC length were considered as 140 nm, 28 nm, and 136 nm, respectively, based on the measured thicknesses for the css(10m-Si/SnO₂/2h-Fe₂O₃) NWs (see the text). The electron affinities for Si, SnO₂, and Fe₂O₃ were considered as 4.05 eV, ~4.8 eV,^[2,3] and ~4.7 eV,^[2] respectively. The doping concentration of p-Si is in the range of 6.7×10^{14} – 1.5×10^{16} cm⁻³ based on its resistivity of 1–20 Ωcm, and of sputtered SnO₂ is in range of 10¹⁹ cm⁻³.^[1] This causes that for the junction between p-Si and n-SnO₂, the depletion region mostly lies in the p-Si NW because of much higher doping concentration of n-SnO₂ layer. The effect of electrolyte pH was considered in the band diagram using the Nernst equation;

$$E(\text{H}^+/\text{H}_2) = -0.059 \times \text{pH} \quad (\text{V vs NHE}) \quad (1)$$

where $E(\text{H}^+/\text{H}_2)$ is the Nernstian (thermodynamic) potential for hydrogen evolution (water reduction). Figure S2-S3 show the approximate energy band diagrams of the p-Si/n-SnO₂/n-Fe₂O₃ css-NW heterojunctions at pre-equilibrium and equilibrium conditions, respectively, and at dark for an electrolyte pH of 7.25. The drawn band diagrams were confirmed by simulation using SCAPS (version 3.1.02) numerical simulation software.

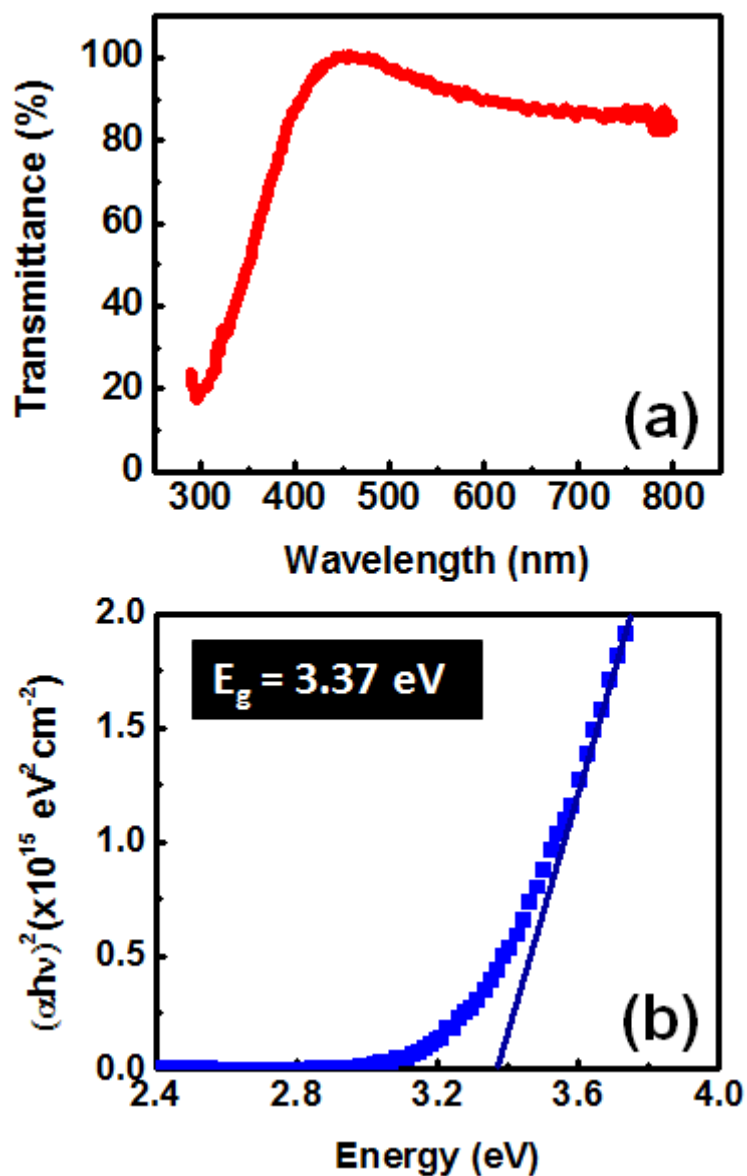


Figure S1. (a) Optical transmittance and (b) Tauc plot of 75 nm thick SnO₂ film sputtered at a RF power of 400 W at room temperature on glass. Extrapolated value gives a SnO₂ band gap of 3.37 eV.

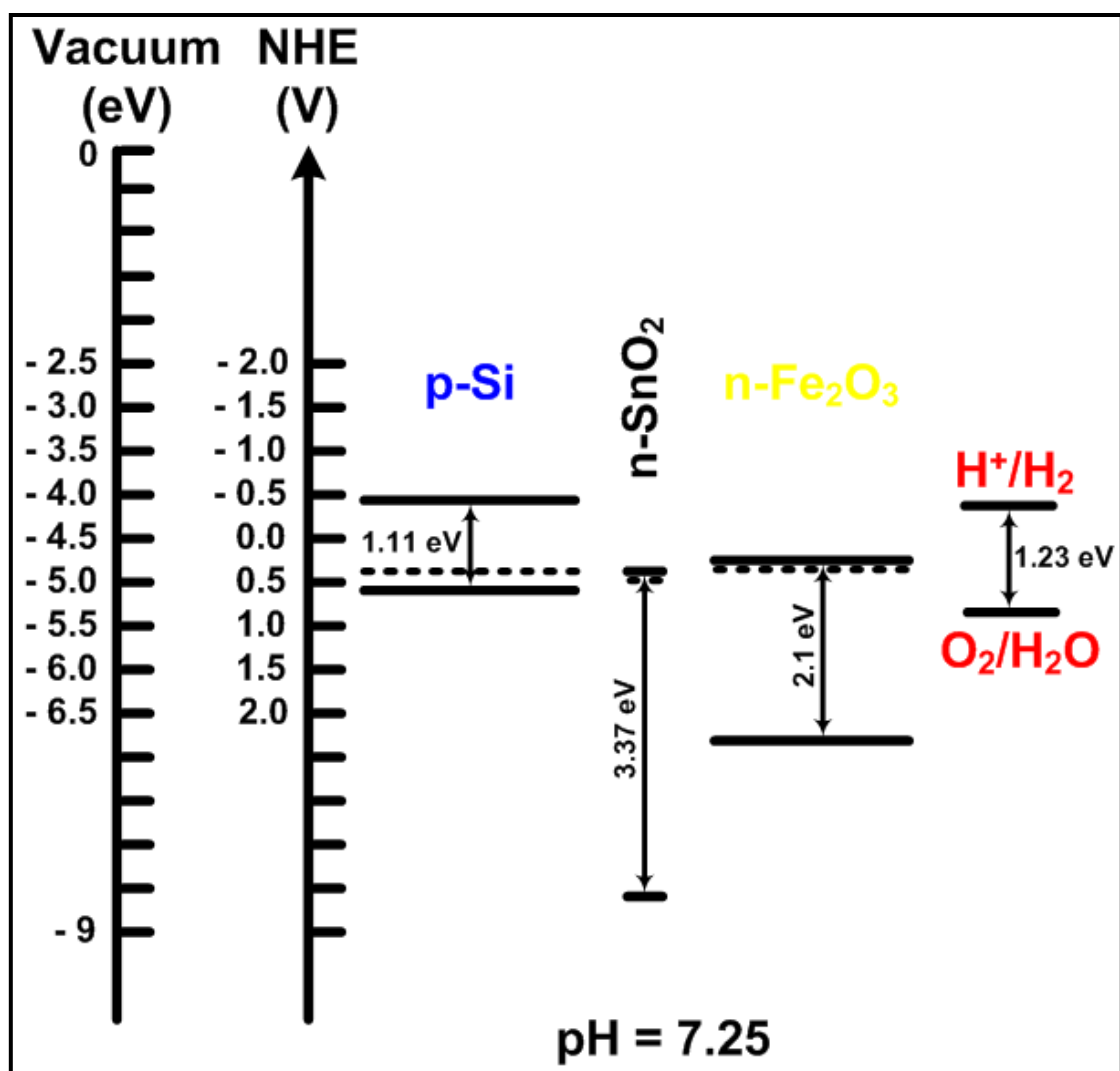


Figure S2. Approximate energy band diagram of p-Si/n-SnO₂/n-Fe₂O₃ css-NW heterojunctions at pre-equilibrium condition and at dark for an electrolyte pH of 7.25.

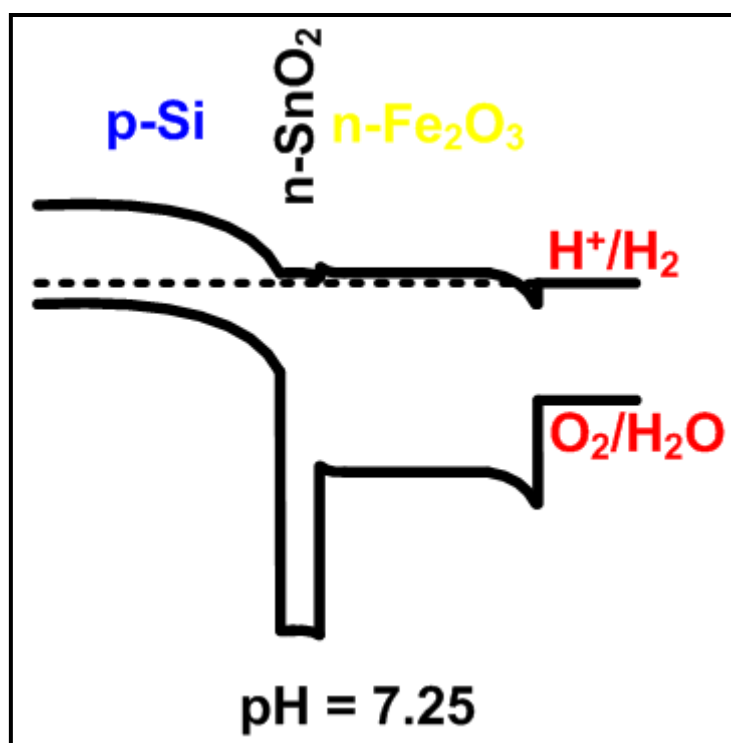


Figure S3. Approximate energy band diagram of p-Si/n-SnO₂/n-Fe₂O₃ css-NW heterojunctions at equilibrium condition and at dark for an electrolyte pH of 7.25.

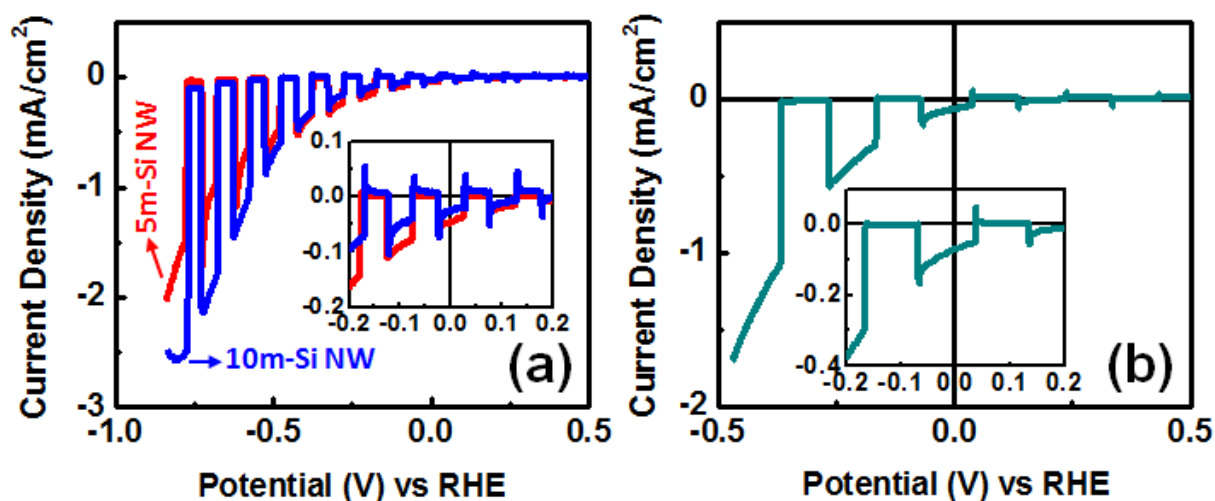


Figure S4. (a) Current density under chopped illumination of $\text{css}(\text{Si}/\text{SnO}_2/2\text{h-Fe}_2\text{O}_3)$ NWs with different Si etching times. These curves are for the same samples shown in Figure 3b in the main text. (b) Current density under chopped illumination of $\text{css}(10\text{m-Si}/\text{SnO}_2/2\text{h-Fe}_2\text{O}_3)$ NWs (the same sample shown in Figure 3c in the main text) measured in 1 M NaOH with pH = 13.5. The insets show the zoom-in plots around 0 V versus RHE.

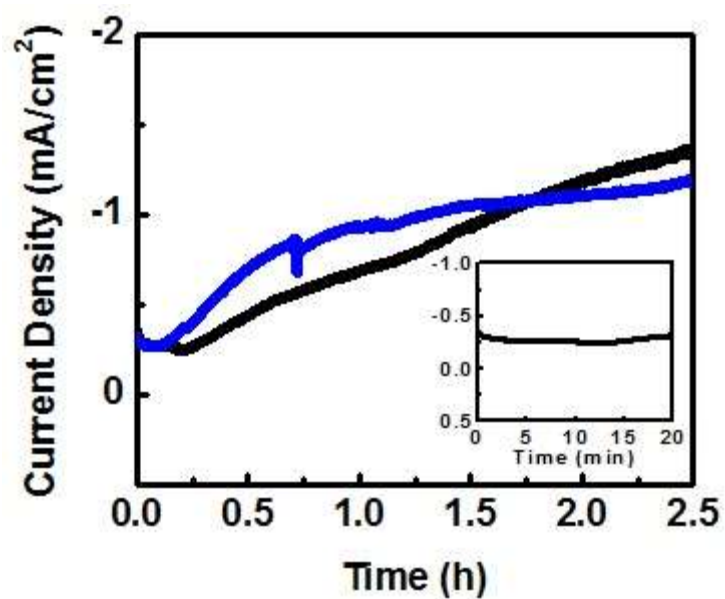


Figure S5. Current density under constant light illumination versus time (stability performance) at -0.33 V versus RHE and in neutral electrolyte of $\text{css}(8.5\text{m-Si}(111)/\text{SnO}_2/2\text{h-Fe}_2\text{O}_3)$ NWs (blue curve; the same curve as shown in Figure 4a in the main text), and $\text{css}(5\text{m-Si}(100)/\text{SnO}_2/2\text{h-Fe}_2\text{O}_3)$ NWs (black curve). Inset exhibits the enlarged first part (0-20 min) of black curve.

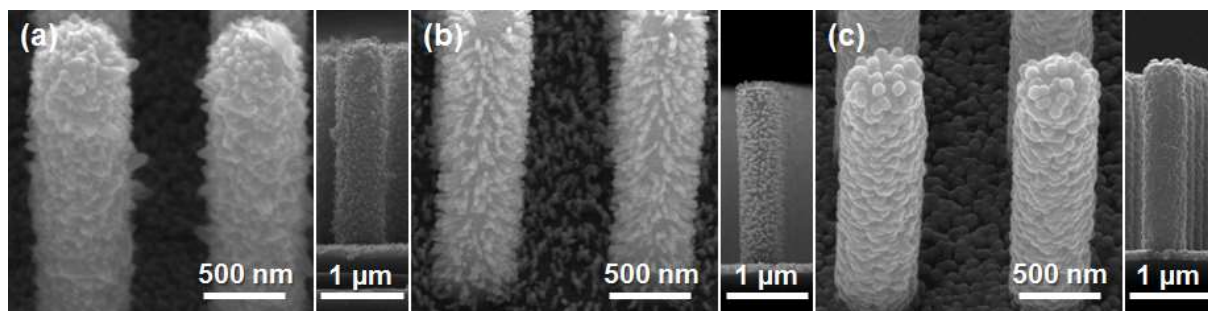


Figure S6. Comparison of different p-Si/metal-oxide NW photocathodes. SEM images of (a) Si/SnO₂/Fe₂O₃ css-NWs, (b) ZnO/Si branched NWs, and (c) TiO₂/Pt-coated ZnO/Si branched NWs. The p-Si(100) NW cores are from 10 mins etching for all the samples in (a)-(c) and they were fabricated under similar conditions. The Fe₂O₃ and ZnO growth times are 2 hrs and 5 mins, respectively. Insets in (a)-(c) show the cross-sectional view images of corresponding samples. The metal-oxide shell in (a)-(c) has almost similar thickness.

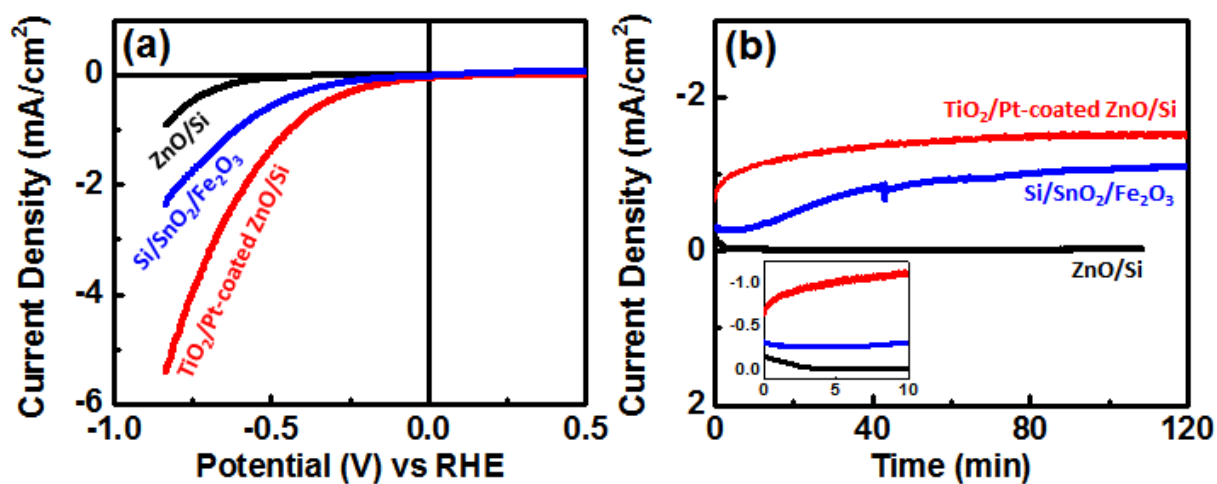


Figure S7. (a) Current density under illumination measured in the neutral electrolyte of Si/SnO₂/Fe₂O₃ css-NWs, ZnO/Si branched NWs, and TiO₂/Pt-coated ZnO/Si branched NWs (the corresponding samples shown in Figure S6). (b) Current density under constant illumination versus time at -0.33 V versus RHE and in the neutral solution of corresponding samples. Inset shows the enlarged first part (0-10 min) of the corresponding curves.

References

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